	0000			
-	3772	recycling or re\$luse or circulat\$3 or	USPAT	2003/12/03 14:11
-	1515	<pre>(introduc\$4 near3 again)) (semiconductor and plasma and (recycle or recycling or re\$1use or circulat\$3 or (introduc\$4 near3 again))) and (emission</pre>	USPAT	2003/12/03 14:18
_	1396		USPAT	2003/12/03
		or recycling or re\$1use or circulat\$3 or (introduc\$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000		14:13
-	487	(((semiconductor and plasma and (recycle or recycling or re\$1use or circulat\$3 or (introduc\$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000) and ((monitor\$3 or analyz\$3 or control\$4 or obtain\$3) with plasma)	USPAT	2003/12/03
_	1	6406924.pn.	USPAT	2003/12/03
	343	or recycling or re\$1use or circulat\$3 or (introduc\$4 near3 again)) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000) and (monitor\$3 or analyz\$3 or control\$4 or obtain\$3) with plasma)) and (etch or etching)	USPAT	2003/12/03
	239	(((((semiconductor and plasma and (recycle or recycling or re\$luse or circulat\$3 or (introduc\$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000) and ((monitor\$3 or analyz\$3 or control\$4 or obtain\$3) with plasma)) and (etch or etching)) and (intensity or amplitude or magnitude)	USPAT	2003/12/03 14:22
-	193	(((((semiconductor and plasma and (recycle or recycling or re\$luse or circulat\$3 or (introduc\$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000) and ((monitor\$3 or analyz\$3 or control\$4 or obtain\$3) with plasma)) and (etch or etching)) and intensity	USPAT	2003/12/03 14:23
_	1	5728253.pn.	USPAT	2003/12/04
-	1	6599842.pn.	USPAT	2003/12/03 16:22
_	1	5565114.pn.	USPAT	2003/12/03 16:22

L Number	Hits	Search Text	DB	Time stamp
-	3169	semiconductor and plasma and (recycle or	USPAT	2003/12/03
		recycling or re\$luse or circulat\$3)		14:10
-	110	(semiconductor and plasma and (recycle or	USPAT	2003/05/14
		recycling or re\$1use or circulat\$3)) and		15:51
		SiF?sub.4	-	1
-	596	semiconductor and plasma and (recycle or	USPAT	2003/05/14
	505	recycling or re\$luse)		15:59
-	535	(semiconductor and plasma and (recycle or	USPAT	2003/05/14 16:09
		recycling or re\$1use)) and (monitor\$3 or analyz\$3 or control\$4)		16:09
_	511	((semiconductor and plasma and (recycle	USPAT	2003/05/14
	311	or recycling or re\$luse)) and (monitor\$3	001111	16:12
		or analyz\$3 or control\$4)) and @ay<=2000		
_	431	(((semiconductor and plasma and (recycle	USPAT	2003/05/14
		or recycling or re\$luse)) and (monitor\$3		15:57
		or analyz\$3 or control\$4)) and @ay<=2000)		
		and flow		
-	175	((((semiconductor and plasma and (recycle	USPAT	2003/05/14
1		or recycling or re\$luse)) and (monitor\$3		17:45
		or analyz\$3 or control\$4)) and @ay<=2000)		
		and flow) and ((silicon adj oxide) or		
		(silicon adj dioxide) or SiO or   SiO?sub.2)		
_	51		USPAT	2003/05/14
_	31	or recycling or re\$luse))	ODEAL	16:05
_	735	semiconductor and plasma and ((gas or	USPAT	2003/05/14
	, , ,	plasma) same (recycle or recycling		16:09
		recycled or recover or recovering or		
		recovered or re\$luse))		
-	684	(semiconductor and plasma and ((gas or	USPAT	2003/05/14
		plasma) same (recycle or recycling		16:09
		recycled or recover or recovering or		
		recovered or re\$1use))) not		
		(semiconductor and (plasma same (recycle		
	602	or recycling or re\$luse)))	USPAT	2003/05/14
-	603	((semiconductor and plasma and ((gas or plasma) same (recycle or recycling	USPAI	16:10
		recycled or recover or recovering or		10.10
		recovered or re\$1use))) not		
		(semiconductor and (plasma same (recycle		
		or recycling or re\$1use)))) and		
		(monitor\$3 or analyz\$3 or control\$4)		
	548	(((semiconductor and plasma and ((gas or	USPAT	2003/05/14
		plasma) same (recycle or recycling		16:14
		recycled or recover or recovering or		
		recovered or re\$1use))) not		
		(semiconductor and (plasma same (recycle		
		or recycling or re\$1use)))) and		
		(monitor\$3 or analyz\$3 or control\$4)) and @ay<=2000		
_	248	((((semiconductor and plasma and ((gas or	USPAT	2003/05/14
	230	plasma) same (recycle or recycling		16:44
		recycled or recover or recovering or		
		recovered or re\$1use))) not		
		(semiconductor and (plasma same (recycle		
		or recycling or re\$1use)))) and		
		(monitor\$3 or analyz\$3 or control\$4)) and		
		@ay<=2000) and ((silicon adj oxide) or		
		(silicon adj dioxide) or SiO or		
		SiO?sub.2)	L	J

_	211	(((((semiconductor and plasma and ((gas or plasma) same (recycle or recycling recycled or recover or recovering or	USPAT	2003/05/14 16:44
	İ	recovered or resluse))) not		
	ŀ	(semiconductor and (plasma same (recycle		
	:	or recycling or re\$1use)))) and (monitor\$3 or analyz\$3 or control\$4)) and		
		@ay<=2000) and ((silicon adj oxide) or		
		(silicon adj dioxide) or SiO or		
_	165	SiO?sub.2)) and @py<=2001   (((((semiconductor and plasma and ((gas	USPAT	2003/05/14
		or plasma) same (recycle or recycling		17:44
	Ì	recycled or recover or recovering or recovered or re\$luse))) not		
		(semiconductor and (plasma same (recycle		
į.		or recycling or re\$1use)})) and		
		(monitor\$3 or analyz\$3 or control\$4)) and (@ay<=2000) and ((silicon adj oxide) or		
		(silicon adj dioxide) or SiO or		
	1	SiO?sub.2)) and @py<=2001) and (etch or		
_	4659	etching) plasma with (monitor or monitoring or	USPAT	2003/05/14
	1000	analyze or analyzing or monitored)	ODEAL	17:45
-	801	(plasma with (monitor or monitoring or	USPAT	2003/05/14
		analyze or analyzing or monitored)) and ((silicon adj oxide) or (silicon adj		17:45
		dioxide) or SiO or SiO?sub.2)		
-	552	((plasma with (monitor or monitoring or	USPAT	2003/05/14
		analyze or analyzing or monitored)) and ((silicon adj oxide) or (silicon adj	i	17:47
	1	dioxide) or SiO or SiO?sub.2)) and (etch	ļ	
	200	or etching)	HCDAM	2003/05/15
	298	(((plasma with (monitor or monitoring or analyze or analyzing or monitored)) and	USPAT	08:49
		((silicon adj oxide) or (silicon adj		
		dioxide) or SiO or SiO?sub.2)) and (etch or etching)) and ((flow adj rate) or	İ	
	l.	sccm)		
-	287	((((plasma with (monitor or monitoring or	USPAT	2003/05/14
	ļ	analyze or analyzing or monitored)) and ((silicon adj oxide) or (silicon adj		17:55
		dioxide) or SiO or SiO?sub.2)) and (etch		
		or etching)) and ((flow adj rate) or		
		sccm)) not ((((((semiconductor and plasma and ((gas or plasma) same (recycle		
		or recycling recycled or recover or	İ	
		recovering or recovered or re\$1use))) not (semiconductor and (plasma same (recycle		
1	}	or recycling or re\$luse)))) and	1	 
		(monitor\$3 or analyz\$3 or control\$4)) and		
1		@ay<=2000) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or	9	
	İ	SiO?sub.2)) and @py<=2001) and (etch or		
	222	etching))	TAGINAM	2003/05/15
ļ -	298	(((plasma with (monitor or monitoring or analyze or analyzing or monitored)) and	USPAT	2003/05/15 08:51
1		((silicon adj oxide) or (silicon adj		
		dioxide) or SiO or SiO?sub.2)) and (etch or etching)) and ((flow adj rate) or		
		or etching); and ((frow ad) rate; or   sccm)		
-	192	((((plasma with (monitor or monitoring or	USPAT	2003/05/15
1		analyze or analyzing or monitored)) and ((silicon adj oxide) or (silicon adj		09:39
1		dioxide) or SiO or SiO?sub.2)) and (etch		
		or etching)) and ((flow adj rate) or		
_	1	sccm) ) and @py<=2000  5347460.pn.	USPAT	2003/05/15
				09:32
-	2	("6081334"   "6406924").PN.	USPAT	2003/05/15
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